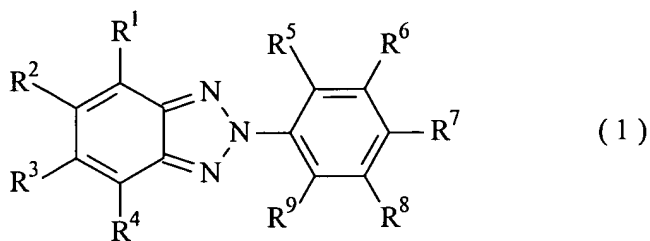


CLAIMS

1. An improver for adhesion of a photosensitive resin composition to a substrate, which consists of an N-phenyl-2H-benzotriazole compound represented by the general formula (1):



wherein R^1 to R^4 each independently represent a hydrogen atom, a halogen atom or a C_{1-5} alkyl group; R^5 to R^9 each independently represent a hydrogen atom, a hydroxyl group, a C_{1-10} alkyl group, an aryl group, a C_{7-12} aralkyl group, $-R^{10}COOR^{11}$, or $-R^{10}CO-(OCH_2CH_2)_n-OH$ provided that at least one of R^5 and R^9 is a hydroxyl group; R^{10} represents a C_{2-5} alkylene group; R^{11} represents a C_{1-8} alkyl group; and n is an integer of 2 to 20.

2. A photosensitive resin composition containing an alkali-soluble resin and a photosensitizer, which comprises at least one of N-phenyl-2H-benzotriazole compounds represented by the general formula (1) in claim 1.

3. The photosensitive resin composition according to claim 2, wherein the alkali-soluble resin is novolak resin, and the photosensitizer is a compound containing a quinonediazide group.